[CK-P.7] Demonstration of wavelength tuning of silica toroid microcavity via additional laser reflow

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Abstract

We demonstrate resonant wavelength tuning of silica toroid microcavity by performing additional laser reflow. Resonant wavelength shift of 160 pm was observed in our experiment.

Background: Silica toroid microcavity

Result: Influences of noisesTO effectWater layerTaper fiber $\Delta\lambda_{TO} \propto \Delta T$ $\Delta\lambda_{water} \propto \Delta R$ $\Delta\lambda_{taper} = f(d)$ Temperature
variationThickness of
water layer: ΔR Cavity-fiber
distance: d



Silica toroid microcavity

- Ultra high quality factor ($Q > 10^8$).
- Possible to fabricate on a chip.
- Prominent candidate for nonlinear optics and single photon devices.



- **Application**: Cavity Quantum Electrodynamics
 - Requires accurate matching of cavity resonance and resonance of single atom.

Cavity resonance tuning method is required.



Maximum wavelength shift from other sources are less than 30 pm.

Background: Wavelength tuning



Wavelength tuning by TO effect

- Metal heater induces refractive index change.
- Repeatable wavelength tuning is possible.
- However, it is not a permanent uning.

D. Almani *et al.,* Appl. Phys. Lett. **85**, 5439 (2004).

Objective of this study:

Developing a method of permanent resonance tuning of silica toroid microcavity based on additional laser reflow.

Principle: Fabrication of disk cavity

Result: Wavelength tuning

1. Fabrication 2. Reflow 3. Measurement



Increase additional reflow power



Experimental procedure

1. Fabricating silica toroid microcavity.

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- 2. Performing additional laser reflow.
- 3. Measuring wavelength shift.
- 4. Back to 2. with increased reflow power.

Observation of blue shift

- When additional reflow with 5W power is performed, wavelength shifts ~160 pm.
- Resonant wavelength tuning based on additional laser reflow is achieved.



Photolithography

By performing photolithography on SOI substrate, SiO₂ pad is fabricated on a Si chip

XeF₂ etching

By performing isotropic XeF₂ Etching, Si is undercutted and SiO₂ disk cavity is formed.



Numerical analysis

- Result of FEM simulation shows that temperature during laser reflow of 5W is on melting point.
- Good agreement with experimental result.

Principle: Laser reflow & Wavelength tuning





Laser reflow process

Absorption in 10.6 μ m: SiO₂ >> Si. Thermal conductivity: SiO₂ << Si. **Only silica disk is heated and toroid shape is formed.**

Additional laser reflow

Additional laser reflow induce additional shrinkage.







Shrinkage results resonant wavelength shift. $\lambda_{\rm m} = 2\pi n R/m$

Laser reflow condition

- Calculated maximum temperature by using FEM (COMSOL multiphysics). Maximum temperature greatly depends on reflowpower.
- "Reflow power" is the key for post-processing.

Conclusion & Future works

Resonant wavelength blue shift of 160 pm was observed in silica toroid microcavity. Further optimization on additional reflow condition and suppression of noises are desired.

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